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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFERMATION NO
09/615,159	07/13/2000	Marc J. Madou	M-2	4896
27304 759			EXAM	INER
CORWIN R. H. THE PARK, SU			BARRECA,	NTCOLE M
25 MANN DRIV KENTFIELD, C			ART UNIT	PAPER NUMBER

DATE MAILED: 01/20/2004

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)		
Office Action Summary	09/615,159	MADOU, MARC J.		
- Canada Gammary	Examiner	Art Unit		
-	Nicole M. Barreca	1756		
The MAILING DATE of this communication Period for Reply				
A SHORTENED STATUTORY PERIOD FOR RI THE MAILUNG DATE OF THIS COMMUNICATIO - Extensions of term may be available under the previouse of 27 of after 80% (8) BOUTTES from the among date of the communication of the STATE - If NO period for retry is specified above, the maximum statutory - If all the level which the safe of contracted periods for regly will, by a feature to reply which the safe or contracted periods for regly will, by a feature to reply which the safe or contracted periods for regly will, by - If all the level which the safe or the STATE of the STATE - If the STATE of the STATE of the STATE of the STATE - If the STATE of the STATE of the STATE of the STATE - If the STATE of the STATE of the STATE of the STATE of the STATE - If the STATE of the STATE	ON. 1R 1,135(a) In no event, however, may a n n a reply within the statutory minimum of thing end will apply and will expre SIX (a) MON	aply be finely filed (30) days will be considered amply. THS from the meltion date of this communication.		
1) Responsive to communication(s) filed on 1	0 December 2003			
This action is FINAL 2b) ☐ This action is non-final.				
 Since this application is in condition for allo closed in accordance with the practice und 	Winner award for from a	rs, prosecution as to the merits is		
Disposition of Claims	ioi Ex parie Guayie, 1935 C.D.	11, 463 O.G. 213.		
4) Claim(s) 1-22 is/are pending in the applicat	Na			
4a) Of the above daim(s) 11-22 is/are without	uon.			
5) Claim(s) is/are allowed.	rawn from consideration.			
6)⊠ Claim(s) 1-10 is/are rejected				
7) Claim(s) is/are objected to.				
Claim(s) 1-22 are subject to restriction and/				
Application Papers	or election requirement.			
The state of the s				
9) The specification is objected to by the Exam	iner.			
10) The drawing(s) filed on 13 July 2000 is/are:	 a)	d to by the Examiner.		
Applicant may not request that any objection to t	the drawing(s) be held in abeyano	e. See 37 CFR 1.85(a),		
Replacement drawing sheet(s) including the con	rection is required if the drawing(s	is objected to. See 37 CFR 1.121(d).		
The Gath of declaration is objected to by the	Examiner. Note the attached of	Office Action or form PTO-152.		
riority under 35 U.S.C. §§ 119 and 120				
12) Acknowledgment is made of a claim for fore	ign priority under 35 U.S.C. §	119(a)-(d) or (f).		
Certified copies of the priority docume Certified copies of the priority docume	ents have been received.			
		olication No.		
 See the attached detailed Office action for a till 	et of the cortifical annual and	ceived.		
since a specific reference was included in the 37 CFR 1.78.	stic priority under 35 U.S.C. § first sentence of the specificati	119(e) (to a provisional application) on or in an Application Data Sheet.		
a) The translation of the foreign language p	provisional application has bee	n received.		
14) Acknowledgment is made of a claim for dome- reference was included in the first sentence of				

11 Prior 12

Interview Summary (PTO-413) Paper No(s).
 Notice of Informal Patent Application (PTO-152)
 Other:

Application/Control Number: 09/615.159 Art Unit: 1756

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DETAILED ACTION

- 1. Applicant's election without traverse of Group I, claims 1-10 and 20-22 in Paper No. 12/10/2003 is acknowledged, as well as applicant's election without traverse of Group I, claims 1-10 in Paper No. 12/10/2003 are acknowledged.
- Claims 11-22 are withdrawn from further consideration pursuant to 37 CFR 2. 1.142(b) as being drawn to nonelected inventions, there being no allowable generic or linking claim. Elections were made without traverse in Paper No. 12/10/2003

Specification

3 The abstract of the disclosure is objected to because it is longer than 150 words. Correction is required. See MPEP § 608.01(b).

Claim Rejections - 35 USC § 103

4 The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

- 5. Claims 1-10 are rejected under 35 U.S.C. 103(a) as being unpatentable over Holland (US 4765864) in view of Chumbers (US 3772101).
- Holland discloses a method for making an electrochemical cell. Electrochemical cell 10 is constructed using semiconductor stab 12, which has a front surface 14 and a back surface 16. First front masking layer 18 and first back masking layer 20 are generally insulative (applicant's substrate layer) and covered by front photoresist layer 22 and back photoresist layer 34 (first and second photoresist matrix layers). The front

photoresist is exposed using a mask to form at least one hole 24 (cavity) and etched to form (larger) well 28 (chamber). The back photoresist layer is exposed to form at least one opening 36 aligned opposite the well 28. Passage 40 or (smaller) well is etched through the exposed part 38 and extended into the slab 12 (col.4, 24-68). A third front insulative layer 42 is provided covering the front side 14 and well 28, terminating at 32 (interface). Conductor 46 (electrode) is deposited in the passage 40 and second front insulative layer 32 is etched. Electrolytic medium 50 is put in well 28 and barrier 52 is formed to cover the well (col.5, 1- col.6, 26). Barrier 52 may be formed of a number of materials and methods such as by heat shrinking (fixing) in place (col.7, 24-67). Holland discloses using positive photoresist layers and not negative photoresist layers. Chumbers teaches that negative and positive photoresist layers may be substituted for each other in a patterning process simply by reversing the opaque areas of the photomask (col.3, 41-52). It would have been obvious to one of ordinary skill in the art to use negative photoresist layers, instead of positive photoresist layers, in the method of Holland because Chumbers teaches that negative and positive photoresist layers may be substituted for each other in a patterning process simply by reversing the opaque areas of the photomask.

7. Please note that because the applicant's claims are written in open language, the prior art cited in a rejection may teach performing additional process steps not claimed by the applicant. See MPEP 2111.03. In addition, the applicant's claims as written do not limit the claims to any specific sequential order and therefore the prior art cited in a rejection may teach performing the applicant's steps in a different order.

Conclusion

- The prior art made of record and not relied upon is considered pertinent to applicant's disclosure. Possin (US 5130263) discloses a patterning method using a selfaligned mask. Staatus (US 2002/0108860) discloses a method for the fabrication of polymeric microfluidic devices.
- Any inquiry concerning this communication or earlier communications from the examiner should be directed to Nicole M. Barreca whose telephone number is 571-272-1378. The examiner can normally be reached on Monday-Thursday (8:00 am-6: 30 pm).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Mark Huff can be reached on 571-272-1385. The fax phone number for the organization where this application or proceeding is assigned is (703) 872-9306.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is 703-308-0661.

> Nicole M. Barreca Examiner Art Unit 1756

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1/12/04